

### INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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APPLICANT  
**Yuichiro SASAKI, et al.**

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(Substitute for form 1449/PTO)

## U.S. PATENT DOCUMENTS

[illegible]

FOREIGN PATENT DOCUMENTS

[illegible]

## OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.
		P. Roca i CABARROCAS, "Plasma enhanced chemical vapor deposition of silicon thin films for large area electronics," Current Opinion in Solid State and Materials Science 5 (2002) 439-444

EXAMINER  
/George Fourson/

DATE CONSIDERED  
09/30/2010

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

1 Applicant's unique citation designation number (optional). 2 Applicant is to place a check mark here if English language Translation is attached

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